

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of) Attorney Docket No.: **SOEI0021**
Ken SAWABE et al.)
Serial No.: 10/595,920) Confirmation No. 9014
Filed: May 19, 2006) Group Art Unit: 1795
For: PHOTOSENSITIVE RESIN) Examiner: Amanda C. WALKE
COMPOSITION, PHOTOSENSITIVE)
ELEMENT, RESIST PATTERN)
FORMING METHOD AND PROCESS) Date: July 13, 2009
FOR MANUFACTURING PRINTED)
CIRCUIT BOARD)

TELEPHONE INTERVIEW SUMMARY (F)

MAIL STOP: ISSUE FEE

United States Patent and Trademark Office
Customer Service Window
Randolph Building
401 Dulany Street
Alexandria, VA 22314

Sir:

In view of the telephone interview conducted on July 13, 2009 between Applicants' attorney, Wesley Ashton, and Examiner Amanda Walke (571-272-1337), please enter the following remarks in the application identified above in accordance with MPEP § 713.04:

Remarks/Arguments begin on page 2 of this paper.